

Electronic Supplementary Information (ESI)

**Unusual enhancement in efficiency of DSSC upon  
modifying photoanode with reduced graphene oxide**

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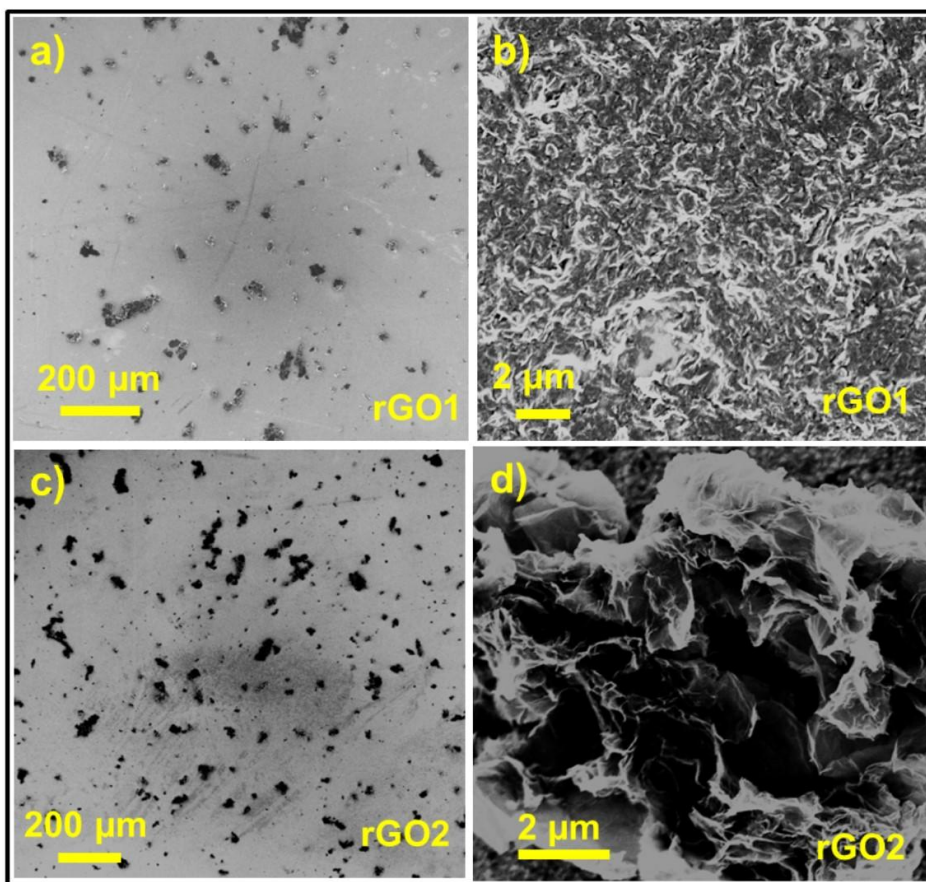
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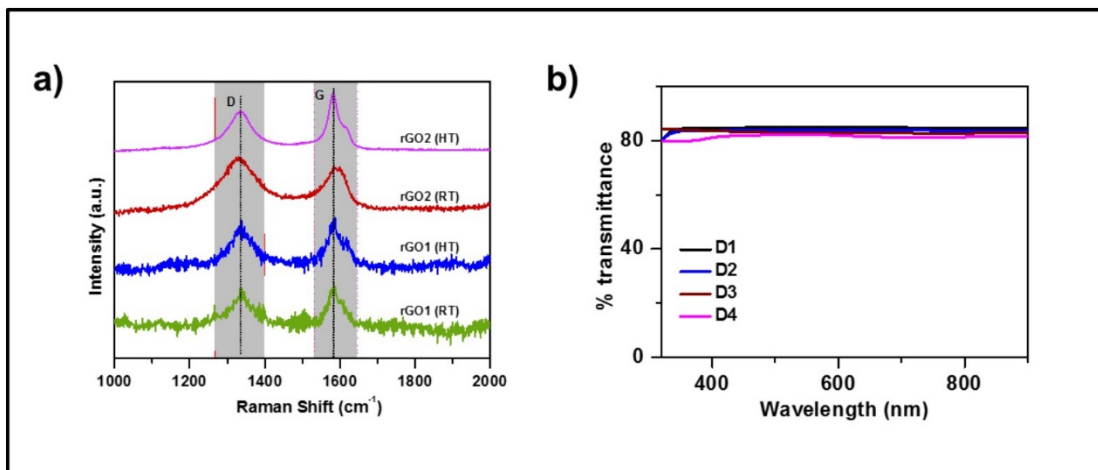
**Table S1** Literature survey of different materials used for enhancement in efficiencies of DSSC

Sr. No.	Materials used for Photoanode	PCE (%)	Features of Materials used to improve efficiency in DSSC	Ref.
1	TiO <sub>2</sub>	5.01	<ul style="list-style-type: none"> <li>● <b>Active material used- 2D Graphene oxide</b></li> <li>● <b>Active material preparation method-</b> Graphite with KMnO<sub>4</sub> as reducing agent</li> <li>● <b>Anode fabrication-</b> 0.6 % weight mixed during TiO<sub>2</sub> paste preparation</li> <li>● Morphology- 2D</li> <li>● 2D materials is more beneficial when compared with 1D</li> </ul>	1
	Grapheneoxide in TiO <sub>2</sub>	6.97		
2	TiO <sub>2</sub>	5.78	<ul style="list-style-type: none"> <li>● <b>Active material used- RGO</b></li> <li>● <b>Active material preparation method-</b> single-layer graphene oxide (SGO) to RGO by heat treatment</li> <li>● <b>Anode fabrication-</b> 3 % weight mixed during TiO<sub>2</sub> paste preparation</li> <li>● Morphology- not explained</li> </ul>	2
	RGO in TiO <sub>2</sub>	7.49		
3	TiO <sub>2</sub>	0.32	<ul style="list-style-type: none"> <li>● <b>Active material used- Graphene sheet</b></li> <li>● <b>Active material preparation method-</b> Graphite to GO and further exploited to Graphene sheets via sonication</li> <li>● <b>Anode fabrication-</b> 0.01-0.05 mg/mL mixed in TiO<sub>2</sub> suspension</li> <li>● Morphology- single sheets</li> </ul>	3
	Graphene sheets in TiO <sub>2</sub>	1.68		
4	TiO <sub>2</sub>	8.45	<ul style="list-style-type: none"> <li>● <b>Active material used- Graphene Purchased</b></li> <li>● <b>Active material preparation method-</b> NA</li> <li>● <b>Anode fabrication-</b> 0.1% Graphene in mixed in TiO<sub>2</sub> suspension</li> <li>● Morphology- agglomerate of Graphene and TiO<sub>2</sub></li> </ul>	4
	Graphene in TiO <sub>2</sub>	9.45		
5	ZnO	2.31	<ul style="list-style-type: none"> <li>● <b>Active material used- Graphene oxide</b></li> <li>● <b>Active material preparation method-</b> Graphite to GO by modified Hummers method</li> <li>● <b>Anode fabrication-</b> 1.2 wt % of graphene scaffolds incorporated into ZnO hierarchically structured nanoparticle (HSN) (In situ generation)</li> </ul>	5
	Grapheneoxide in ZnO	3.19		
6	TiO <sub>2</sub>	4.2	<ul style="list-style-type: none"> <li>● <b>Active material used- rGO</b></li> <li>● <b>Active material preparation method-</b> Graphite to GO by modified Hummers methods</li> <li>● <b>Anode fabrication-</b> 0.75 Wt% mixed during TiO<sub>2</sub> paste preparation</li> </ul>	6
	rGO in TiO <sub>2</sub>	5.5		
7	TiO <sub>2</sub>	4.54	<ul style="list-style-type: none"> <li>● <b>Active material used- multi-walled carbon nanotubes</b></li> <li>● <b>Active material preparation method-</b> Graphite to multi-walled carbon nanotubes by Staudenmaier's method followed by heat treatment</li> <li>● <b>Anode fabrication-</b> composite of multi-walled carbon nanotubes pastes were prepared for doctor blading TiO<sub>2</sub> particle</li> </ul>	7
	multi-walled carbon nanotubes in TiO <sub>2</sub>	6.11		
8	TiO <sub>2</sub>	1.79	<ul style="list-style-type: none"> <li>● <b>Active material used- Graphene oxide</b></li> <li>● <b>Active material preparation method-</b> Modified Hummers methods</li> <li>● <b>Anode fabrication-</b> 0.21 wt % GO</li> </ul>	8
	Grapheneoxide in TiO <sub>2</sub>	2.78		

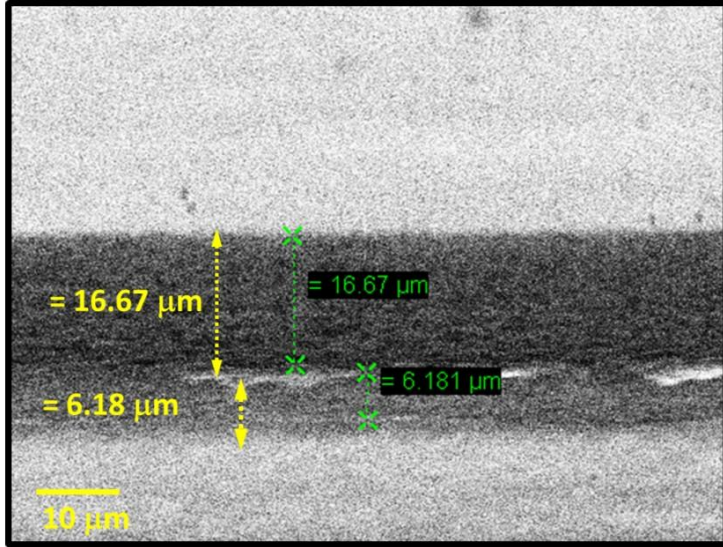
			mixed with TiO <sub>2</sub> particle	
9	TiO <sub>2</sub> Fibers	6.3	<ul style="list-style-type: none"> <li>● <b>Active material- Graphene Purchased</b></li> <li>● <b>Active material preparation method- NA</b></li> <li>● <b>Anode fabrication-</b> Electrospinning of conductive TiO<sub>2</sub>-graphene composites in combination with PVP as a carrier solution resulting in well-defined and structurally stable fibers.</li> </ul>	9
	Graphene in TiO <sub>2</sub> Fibers	7.6		
10	TiO <sub>2</sub>	6.08	<ul style="list-style-type: none"> <li>● <b>Active material used- rGO</b></li> <li>● <b>Active material preparation method-</b> Chemically reduced graphene oxide</li> <li>● <b>Anode fabrication-</b> Simple spin coating of RGO at FTO/TiO<sub>2</sub> interface</li> </ul>	Present work
	rGO spincoated at Interface	8.19		
11	TiO <sub>2</sub>	6.08	<ul style="list-style-type: none"> <li>● <b>Active material used- rGO</b></li> <li>● <b>Active material preparation method-</b> Chemically reduced graphene oxide</li> <li>● <b>Anode fabrication-</b> Simple spin coating of RGO at FTO/ TiO<sub>2</sub> interface</li> </ul>	Present work
	rGO spincoated at Interface	8.03		



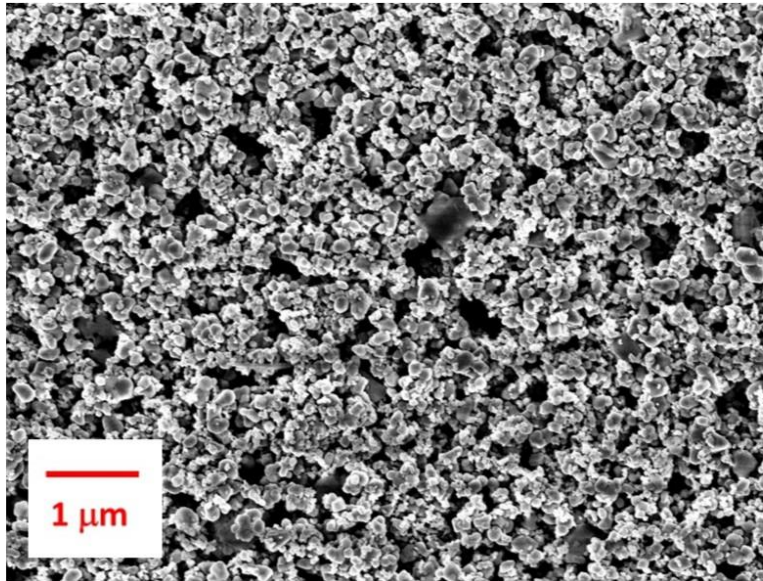
**Figure S1** FESEM images of spin coated rGO1 (a) and rGO2 (c) on FTO after calcination at 500 °C in open air whereby rGO particles are clearly visible with retention of morphology (zoomed-in FESEM images are presented b and d). Calcination was carried out to check the sustainability of rGO materials in photoanode fabrication process.



**Figure S2** (a) Raman spectra of rGO1 and rGO2 where RT indicate before heating and HT after heating at 500 °C in open air, respectively. (b) Absorbance spectra of blank FTO (D1), TiCl<sub>4</sub> treated (D2), spin coated rGO1 (D3) and rGO2 (D4) systems.



**Figure S3** Cross-sectional FESEM image of the photoanode of the D3 device.



**Figure S4** FESEM image of the photoanode of the D3 device.



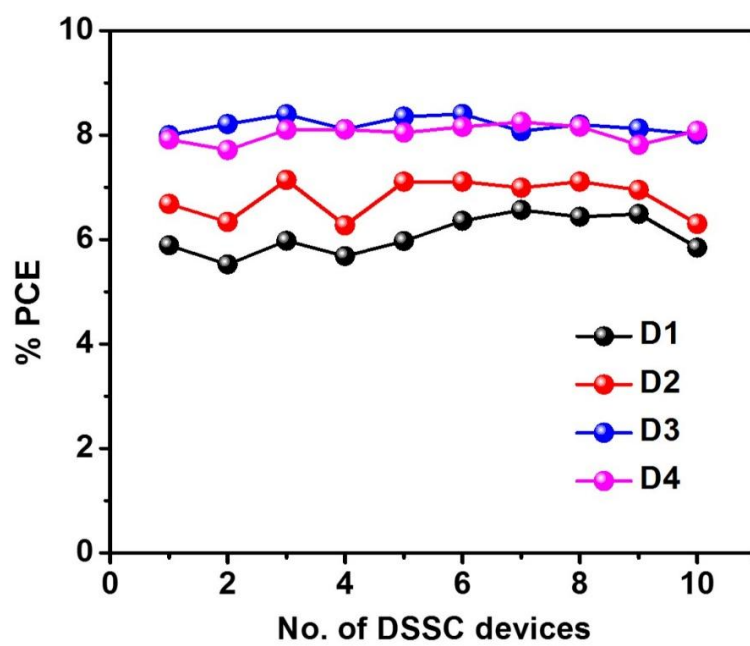
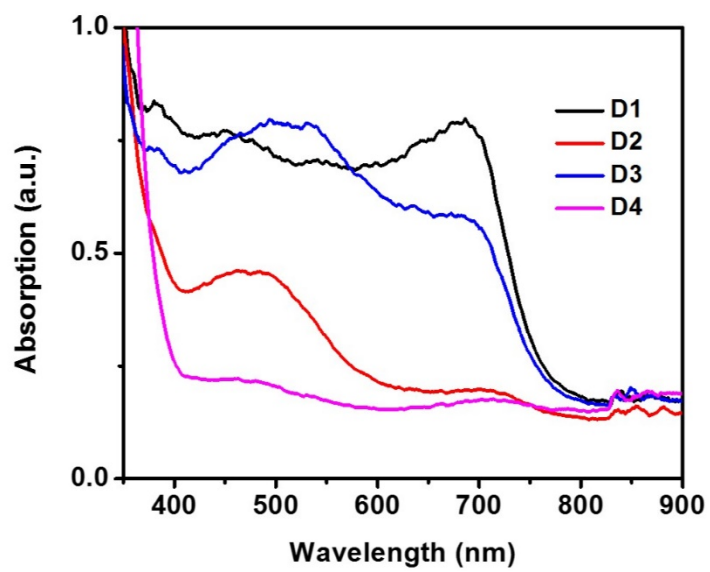
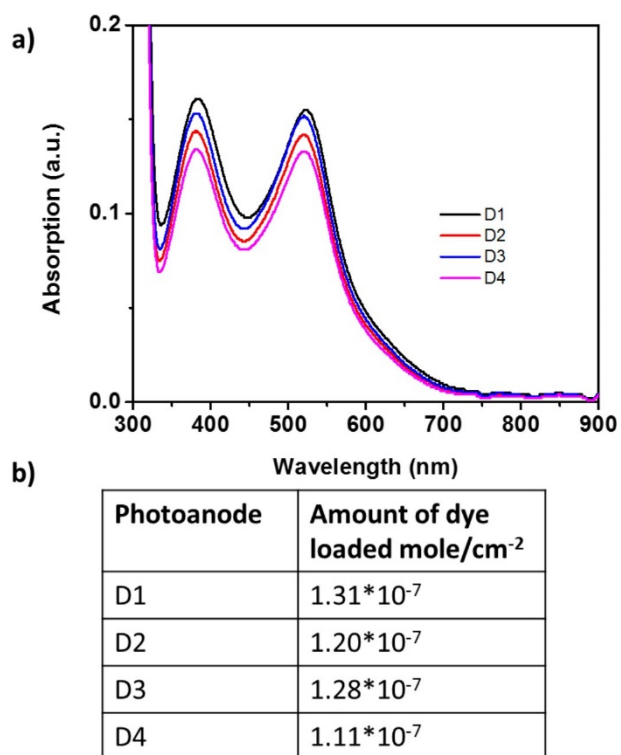


Figure S5 % PCE values of each 10 devices of D1, D2, D3 and D4.



**Figure S6** Solid-state UV-vis spectra of photoanodes of D1, D2, D3 and D4 devices.



**Figure S7** (a) UV-vis spectra of de-absorbed dye from photoanodes of D1, D2, D3 and D4 devices. (b) Table showing the amount of dye loading in D1, D2, D3 and D4 devices.

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